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**Clear Metals Inc. (CMI) announces successful testing continuous in-line metal oxide deposition process based on the company's proprietary technology. New technology removes restrictions on the maximum substrate size as well as enables a potential break-through in roll-to-roll processing in flexible display manufacturing.**

The CMI development team has announced successful completion of experimental testing of the next generation of its proprietary metal oxide deposition process and equipment. The new equipment design was developed to scale CMI's metal oxide deposition capabilities beyond previously demonstrated Gen 2 glass substrate size (360 mm x 465 mm).

By successfully implementing an in-line continuous metal oxide deposition process and equipment design CMI has now demonstrated the fundamental possibility to continue meeting display and touch panel industry requirements as manufacturers are moving to ever increasing substrate sizes in pursuit of cost reduction and process optimization.

Furthermore, in-line continuous printing of metal oxide films based on CMI's proprietary low temperature wet-process technology constitutes a potential breakthrough that could accelerate commercialization of certain flexible electronics devices. CMI has filed an additional patent application in respect of this new development thus expanding its total IP base to three independent patents and patent applications.

The results constitute an important milestone in development of the CMI's technology. Both the touch panel and AMOLED industries are currently relying on high cost magnetron sputtering process as one of the critical display screen manufacturing steps - deposition of TCO films. While sputtering is a well-established technology it comes with a number of critical limitations including:

1. High process temperature
2. Low material utilization
3. High equipment cost
4. High maintenance cost and long down time

Today, these limitations are increasingly becoming a hindrance to the industry's drive to improve existing product cost structure as well as to transition to the next generation of display screen technologies. Despite a number of attempts to find alternative solutions to TCO deposition, the industry is yet to identify a lower cost, high throughput and efficiency technology capable of matching performance characteristics of sputtered TCO films.

CMI's proprietary patent pending technology holds the promise of offering such alternative solution. Over the course of the last few months the company has obtained experimental results clearly confirming CMI's ability to:

1. Use its proprietary process for TCO deposition on glass substrates;
2. Deliver TCO coatings with electrical, optical as well as thickness uniformity well within industry requirements;
3. Achieve high process speed and efficiency with growth rates up to 100 nm / min and over 98% material utilization; and
4. Deposit TCO coatings at room temperature in crystalline form thus eliminating the need for high temperature annealing steps.

The most recent development of the in-line continuous deposition process and equipment set up further solidifies CMI's position as a technology leader in metal oxide deposition. Armed with these highly promising results the CMI is now looking to engage early adopter customers for the purposes of product sampling and further development.

*Further information on CMI and its proprietary technology is available at [www.clearmetalsinc.com](http://www.clearmetalsinc.com)*